

FULLY INTEGRATED THERMAL INKJET PRINthead

HAVING ETCHED BACK PSG LAYER



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ABSTRACT OF THE DISCLOSURE

Described herein is a monolithic printhead formed using integrated circuit techniques. Thin film layers (24, 40-50), including ink ejection elements (24), are formed on a top surface of a silicon substrate (20). The various layers are etched to provide conductive leads (25) to the ink ejection elements (24). At least one ink feed hole (26) is formed through the thin film layers (24, 40-50) for each ink ejection chamber (30). A trench (36) is etched in the bottom surface of the substrate (20) so that ink (38) can flow into the trench and into each ink ejection chamber (30) through the ink feed holes (26) formed in the thin film layers. An orifice layer (28) is formed on the top surface of the thin film layers (24, 40-50) to define the nozzles (34) and ink ejection chambers (30). A phosphosilicate glass (PSG) layer (42), providing an insulation layer beneath the resistive layers (24), is etched back from the ink feed holes (26) and is protected by a passivation layer (46) to prevent the ink (38) from interacting with the PSG layer (42). Other layers may also be protected from the ink (38) by being etched back.

Figure 2